10/009,884

		1009,884		
L Numb			DB	Time stamp
1	45	(Code of the state of the stat	USPAT	Time stamp 2004/09/03 11:06
		and ((thiocyanic adj acid) (thiosulfuric		
		adj acid) thiourea thio\$1ehter thiol		
		(sulfur near3 halide) (sulfur near3	-	
2	1605	oxyhalide) (halogenosulfonic))		
	1685	((over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT	2004/09/03 10:41
	İ	surface adj treatment) and ((thiocyanic		
		adj acid) (thiosulfuric adj acid) thiourea	İ	
		thio\$lehter thiol (sulfur near3 halide) (sulfur near3 oxyhalide)		
		(halogenosulfonic))		
3	2676	((over\$1print\$3 near3 (coat\$3 varnish\$3))	TIOD N. III	0004/00/00 40
_	20,0	surface adj treatment) and ((thiocyanic	USPAT; US-PGPUB;	2004/09/03 10:41
		adj acid) (thiosulfuric adj acid) thiourea	EPO; JPO;	İ
		thio\$1ehter thiol (sulfur near3 halide)	DERWENT;	
		(sulfur near3 oxyhalide)	IBM_TDB	
		(halogenosulfonic))	1514-156	
4	96	((over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT	2004/09/03 10:41
		surface adj treatment) and ((thiocyanic	OSTAT	2004/09/03 10:41
		adj acid) (thiosulfuric adj acid) thiourea		
		thio\$1ehter thiol (sulfur near3 halide)		
		(sulfur near3 oxyhalide)		
		(halogenosulfonic)) and ink\$1jet		
5	928	((over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT	2004/09/03 10:55
		surface adj treatment) and ((thiocyanic		2001,00,00 10:00
		adj acid) (thiosulfuric adj acid) thiourea		
		thio\$1ehter (sulfur near3 halide) (sulfur		
_		<pre>near3 oxyhalide) (halogenosulfonic))</pre>		
6	96	(((over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT	2004/09/03 10:51
		surface adj treatment) and ((thiocyanic		
	i	adj acid) (thiosulfuric adj acid) thiourea	İ	
		thio\$1ehter thiol (sulfur near3 halide)		
		(sulfur near3 oxyhalide)		
		(halogenosulfonic)) and ink\$1jet) not		
		((over\$1print\$3 near3 (coat\$3 varnish\$3))		
		and ((thiocyanic adj acid) (thiosulfuric		
		adj acid) thiourea thio\$1ehter thiol		
		<pre>(sulfur near3 halide) (sulfur near3 oxyhalide) (halogenosulfonic)))</pre>		
7	5	(("3147301") or ("3033833") or ("2914499")	HODEN	0004/00/00
		or ("2923734") or ("3024221")).PN.	USPAT	2004/09/03 10:52
8	7	(over\$1print\$3 near3 (coat\$3 varnish\$3))	HODAM	0004/00/00 40 55
	, i	and ((thiocyanic adj acid) (thiosulfuric	USPAT	2004/09/03 10:56
		adj acid) thiourea thio\$lehter (sulfur		1
		near3 halide) (sulfur near3 oxyhalide)		
		(halogenosulfonic))		iu
9	7	(over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT;	2004/09/03 10:56
		and ((thiocyanic adj acid) (thiosulfuric	US-PGPUB;	2004/09/03 10:56
		adj acid) thiourea thio\$lehter (sulfur	EPO; JPO;	
	}	near3 halide) (sulfur near3 oxyhalide)	DERWENT;	
		(halogenosulfonic))	IBM TDB	1
10	7	(over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT;	2004/09/03 11:06
		and thiourea	US-PGPUB;	2001,03,03 11.00
			EPO; JPO;	
		j	DERWENT;	
			IBM TDB	
-	14	(("6677006") or ("6596378") or ("6589635")	USPĀT	2004/09/02 17:01
		or ("6698875") or ("6555207") or		, , , , , , , , , , , , , , , , , , , ,
		("6517929") or ("6565952") or ("6652171")		
		or ("6548150") or ("6173646") or		
		("6245422") or ("6174611") or ("5662997")		
	5.0=	or ("5560771") or ("5421871")).PN.		
_	5497	((427/258) or (427/261) or (427/265) or	USPAT;	2004/09/02 17:07
		(427/288) or (427/407.1) or	US-PGPUB;	
		(427/411)).CCLS.	EPO; JPO;	
			DERWENT;	
			IBM_TDB	

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_	0	<pre>(over\$1print\$3 near3 (coat\$3 varnish\$3)) same (sulfur thiocyanic thiosulfuric</pre>	USPAT; US-PGPUB;	2004/09/02 17:09
		thiourea thio\$1ehter thio1)	EPO; JPO; DERWENT; IBM TDB	
<u>-</u>	1041	(over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT; US-PGPUB;	2004/09/02 17:09
			EPO; JPO; DERWENT; IBM TDB	
_	119	(over\$1print\$3 near3 (coat\$3 varnish\$3)) and (sulfur thiocyanic thiosulfuric thiourea thio\$1ehter thio1)	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/02 17:11
_	5	((over\$1print\$3 near3 (coat\$3 varnish\$3)) and (sulfur thiocyanic thiosulfuric	IBM_TDB USPAT; EPO; JPO;	2004/09/02 17:12
_	119	thiourea thio\$1ehter thio1)) and ink\$1jet (over\$1print\$3 near3 (coat\$3 varnish\$3)) and (sulfur (thiocyanic adj acid) (thiosulfuric adj acid) thiourea	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/02 17:31
		thio\$lehter thiol (sulfur near3 halide) (sulfur near3 oxyhalide) (halogenosulfonic))	DERWENT; IBM_TDB	
-	5	((over\$1print\$3 near3 (coat\$3 varnish\$3)) and (sulfur (thiocyanic adj acid) (thiosulfuric adj acid) thiourea thio\$1ehter thiol (sulfur near3 halide)	USPAT; EPO; JPO; DERWENT	2004/09/02 17:12
_	91		USPAT	2004/09/02 17:45
		and (sulfur (thiocyanic adj acid) (thiosulfuric adj acid) thiourea thio\$lehter thiol (sulfur near3 halide) (sulfur near3 oxyhalide)		
_	143	<pre>(halogenosulfonic)) (over\$1print\$3 near3 (coat\$3 varnish\$3))[ti]</pre>	USPAT; US-PGPUB; EPO; JPO;	2004/09/02 17:32
	,,		DERWENT; IBM TDB	
	0	((over\$1print\$3 near3 (coat\$3 varnish\$3))[ti]) and (sulfur (thiocyanic adj acid) (thiosulfuric adj acid) thiourea thio\$1ehter thiol (sulfur near3 halide)	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/02 17:32
-	0	<pre>(sulfur near3 oxyhalide) (halogenosulfonic)) (over\$1print\$3 near3 (coat\$3</pre>	IBM_TDB USPAT;	2004/09/02 17:32
		varnish\$3))[ti] and (sulfur (thiocyanic adj acid) (thiosulfuric adj acid) thiourea thio\$lehter thiol (sulfur near3 halide)	US-PGPUB; EPO; JPO; DERWENT;	
		<pre>(sulfur near3 oxyhalide) (halogenosulfonic))</pre>	IBM_TDB	